

DATA MANAGEMENT METHOD FOR RETICLE/MASK WRITING

Abstract of the Disclosure

5 A method of translating device layout data to a format for a mask writing tool includes the acts of reading a file defining a number of cells that represent structures on the device. One or more cells are selected and one or more modified cells based on the interaction of the selected cells with other cells in the device layout are created. One or more additional cells is created that will create structures on the mask that are not formed by writing files corresponding to the modified cells and areas that prevent extraneous structures from being formed on the mask at a selected location by the writing of the files corresponding to the modified cells. A jobdeck 10 for the mask writing tool is created that indicates where the files corresponding to modified cells and the one or more additional cells should be written to create one or more masks or reticles.

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